Accepted Manuscript

Miniaturized fracture experiments to determine the toughness of individual films in a multilayer system

R. Treml, D. Kozic, R. Schöngrundner, O. Kolednik, H.-P. Gänser, R. Brunner, D. Kiener

PII: S2352-4316(16)00011-0

DOI: http://dx.doi.org/10.1016/j.eml.2016.01.004

Reference: EML 108

To appear in: Extreme Mechanics Letters

Received date: 26 November 2015 Revised date: 19 January 2016 Accepted date: 23 January 2016



Please cite this article as: R. Treml, D. Kozic, R. Schöngrundner, O. Kolednik, H.-P. Gänser, R. Brunner, D. Kiener, Miniaturized fracture experiments to determine the toughness of individual films in a multilayer system, *Extreme Mechanics Letters* (2016), http://dx.doi.org/10.1016/j.eml.2016.01.004

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.

ACCEPTED MANUSCRIPT

Miniaturized Fracture Experiments to Determine the Toughness of Individual Films in a Multilayer System

R. Treml¹, D. Kozic², R. Schöngrundner², O. Kolednik³, H.-P. Gänser², R. Brunner², D. Kiener¹

Abstract

Recently, the miniaturization of devices in the field of microelectronics has become more and more important. This also implies an increased complexity of the devices, where multilayer thin film systems play a major role. The use of various material combinations leads to the development of residual stresses, potentially causing cracks. Therefore, to prevent failures a thorough understanding of material properties such as the fracture toughness at small scales is indispensable, as these may differ significantly from bulk values. In this study we use miniaturized fracture tests to investigate the fracture behaviour of Cu-W-Cu and W-Cu-W trilayer thin film systems, having a thickness of 500 nm per individual W or Cu layer. The films are subjected to differences in elastic properties and residual stress gradients that both influence the fracture behaviour and thus have to be included in all considerations. We demonstrate that for the W layers a valid *J*-integral can be evaluated. However, we find that the presented advanced treatment does not allow the extraction of valid fracture mechanical quantities for the Cu layers, pointing out the need to develop a more sophisticated approach for ductile materials.

¹ Department Materials Physics, Montanuniversität Leoben, Austria

² Materials Center Leoben Forschungs GmbH, Leoben, Austria

³ Erich Schmid Institute, Austrian Academy of Sciences, Leoben, Austria

Download English Version:

https://daneshyari.com/en/article/5014565

Download Persian Version:

https://daneshyari.com/article/5014565

Daneshyari.com